

Docket No. 1270.43264X00  
 Serial No. 10/701,448  
April 26, 2005

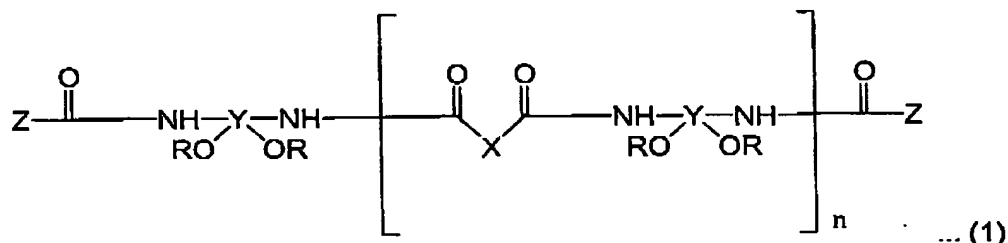
### AMENDMENTS TO THE CLAIMS:

The following listing of claims replaces all prior listings, and all prior versions, of claims in the application.

### LISTING OF CLAIMS:

1. (Currently amended) A photosensitive resin composition comprising:

(A) a heat-resistant polymer represented by general formula (1)



where X represents a divalent organic group; Y represents a tetravalent organic group; Z represents a cyclic compound group free of reactive unsaturated bonds; R represents hydrogen or a monovalent organic group; and n is an integer of 2 to 500 and represents the number of repeating units of the polymer;

(B) a photoreactive compound which generates an acid upon undergoing a reaction with light; and

(C) a solvent,

wherein said photosensitive resin composition is a positive photosensitive resin composition.

2. (Original) The photosensitive resin composition according to claim 1, wherein at least one of the organic groups X and Y is an aromatic group.

Docket No. 1270.43264X00

Serial No. 10/701,448

April 25, 2005

3. (Original) The photosensitive resin composition according to claim 1, wherein the cyclic compound group Z is a compound group having an alicyclic structure.

4. (Original) The photosensitive resin composition according to claim 2, wherein the cyclic compound group Z is a compound group having an alicyclic structure.

5. (Original) The photosensitive resin composition according to claim 3, wherein the compound group having an alicyclic structure has 3 or 4 carbon atoms.

6. (Original) The photosensitive resin composition according to claim 4, wherein the compound group having an alicyclic structure has 3 or 4 carbon atoms.

7. (Original) The photosensitive resin composition according to claim 1, wherein the divalent organic group represented by X comprises at least one divalent group derived from 3-fluoroisophthalic acid, 2-fluoroisophthalic acid, 3-fluorophthalic acid, 2-fluorophthalic acid, 2,4,5,6-tetrafluoroisophthalic acid, 3,4,5,6-tetrafluorophthalic acid, 4,4'-hexafluoroisopropylidenediphenyldicarboxylic acid, perfluorosuberic acid, 2,2'-bis(trifluoromethyl)-4,4'-biphenylenedicarboxylic acid, terephthalic acid, isophthalic acid, 4,4'-oxydiphenyldicarboxylic acid, 5-nitroisophthalic acid, 1,4-naphthalenedicarboxylic acid, 2,6-naphthalenedicarboxylic acid, and 4,4'-biphenyldicarboxylic acid.

8. (Original) The photosensitive resin composition according to claim 1, wherein the tetravalent organic group represented by Y comprises at least one divalent group

Docket No. 1270.43284X00  
Serial No. 10/701,448  
April 25, 2005

derived from 4,4'-diamino-3,3'-dihydroxybiphenyl, 2,2'-bis(3-amino-4-hydroxyphenyl)propane, and 2,2'-bis(3-amino-4-hydroxyphenyl)hexafluoropropane.

9. (Original) The photosensitive resin composition according to claim 1, wherein Z comprises at least one group selected from the group consisting of cyclopropyl, cyclobutyl, 2-phenyl-1-cyclopropyl, 1-phenyl-1-cyclopropyl, 1-benzocyclobutenyl, 2-methylcyclopropenyl, 1-hydroxy-1-cyclopropyl, 1-carboxy-1-cyclopropyl, and 1-carboxy-1-cyclobutyl.

10. (Original) The photosensitive resin composition according to claim 1, wherein the heat-resistant polymer has a weight average molecular weight in the range of 5,000 to 80,000.

11. (Original) A process for forming a relief pattern, comprising:  
applying the photosensitive resin composition according to claim 1 to a support substrate and drying the composition applied to form a photosensitive resin film;  
subjecting the dried photosensitive resin film to exposure;  
subjecting the exposed photosensitive resin film to development using an alkaline aqueous solution; and  
subjecting the developed photosensitive resin film to heating treatment.

12. (Original) An electronic component having an electronic device including at least an interlayer dielectric film layer and a surface protecting film layer,

Docket No. 1270.43264X00

Serial No. 10/701,448

April 25, 2005

wherein at least one of the interlayer dielectric film layer and the surface protecting film layer comprises a resin film formed from the photosensitive resin composition according to claim 1.

13. (Previously presented) An electronic component having an electronic device including at least an interlayer dielectric film and a surface protecting layer,

wherein at least one of the interlayer dielectric film and the surface protecting layer comprises a resin film, and wherein the resin film comprises a patterned film formed by the process according to claim 11.

14. (New) The photosensitive resin composition according to claim 1, wherein said heat-resistant polymer is substantially free of polymerizable C=C double bonds.

15. (New) The photosensitive resin composition according to claim 1, wherein the photoreactive compound generates the acid such that the acid formed increases the solubility in an alkaline aqueous solution of the portion of the resin composition exposed to the light.

16. (New) The photosensitive resin composition according to claim 1, wherein said photoreactive compound is selected from the group consisting of o-quinonediazide compounds, aryl diazonium salts, diaryliodonium salts and triarylsulfonium salts.

Docket No. 1270.43264X00

Serial No. 10/701,448

April 25, 2005

17. (New) The photosensitive resin composition according to claim 1, containing 0.1 to 40 parts by weight of the photoreactive compound per 100 parts by weight of the heat-resistant polymer.